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(21)Application number : 10-142960 (71)Applicant : KAO CORP  
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### (54) MANUFACTURE OF SECONDARY BATTERY NEGATIVE ELECTRODE

#### (57)Abstract:

PROBLEM TO BE SOLVED: To reduce the contact resistance between a current collector and a sintered body in a negative electrode containing silicon as active material by baking a coating film containing silicon and a base material consisting of a conductive metal foil or mesh.

SOLUTION: To manufacture a secondary battery negative electrode, a binder and a solvent are added to a negative electrode material containing silicon to prepare a slurry. The slurry is then applied to a base material consisting of a conductive metal foil or mesh, and the solvent is removed to produce a coating film. The coating film is integrated into the base material and sintered by baking under non-oxidizing atmosphere. Since the contact area of the interface between the sintered body and the current collector is increased to integrate them together by baking under non-oxidizing atmosphere, the contact resistance between the sintered body and the current collector can be reduced, and a negative electrode consisting of a thin film improved in conductivity can be provided.

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